

Outline

Motivation

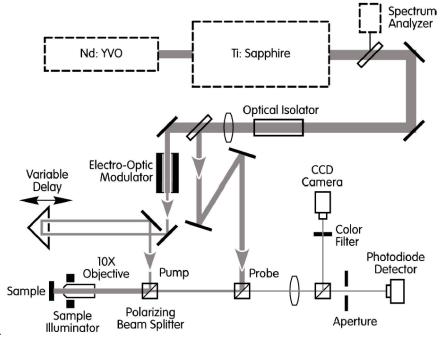
- Anisotropy of the apparent thermal conductivity in a TDTR measurement of Si
- II. Manipulate the spectrum of heat carriers using B and Ge doping of Si
- III. Consequences for TDTR measurements of interface thermal conductance

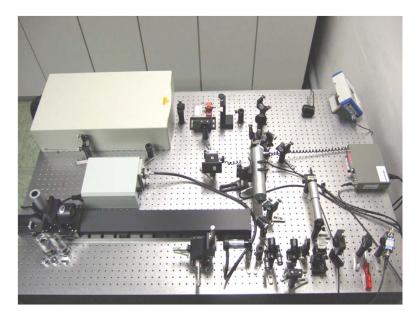
Conclusions

Time domain thermoreflectance since 2003

- Improved optical design
- Normalization by out-ofphase signal eliminates artifacts, increases dynamic range and improves sensitivity
- Exact analytical model for Gaussian beams and arbitrary layered geometries
- One-laser/two-color approach tolerates diffuse scattering

Clone built at Fraunhofer Institute for Physical Measurement, Jan. 7-8 2008

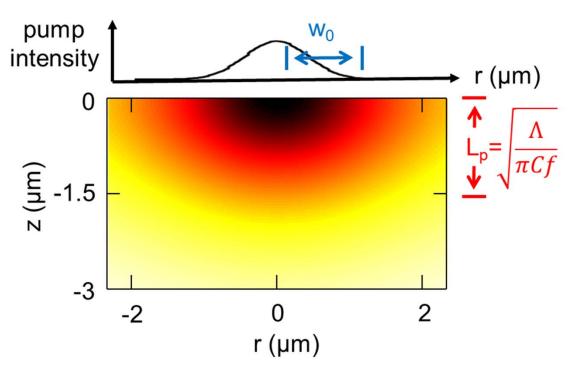




TDTR and phonon mean-free-path spectroscopy

- Time-domain thermoreflectance (TDTR) is a powerful method but we do not deeply understand what we are measuring.
 - When is Fourier's law an adequate description and when does it fail?
 - Answer depends on the details of the sample, the dimensionality of the heat conduction, and the transport properties of the metal/sample interface.
- Bring it to the next level: If we can quantitatively understand the failure of the Fourier's law, can we use that information to characterize the distribution of phonon-mean free paths?
 - The metal/sample interface complicates the problem and the answer depends on the details of the sample.

TDTR and phonon mean-free-path spectroscopy



L_P = thermal penetration depth f = heating frequency

 w_0 = laser spot size

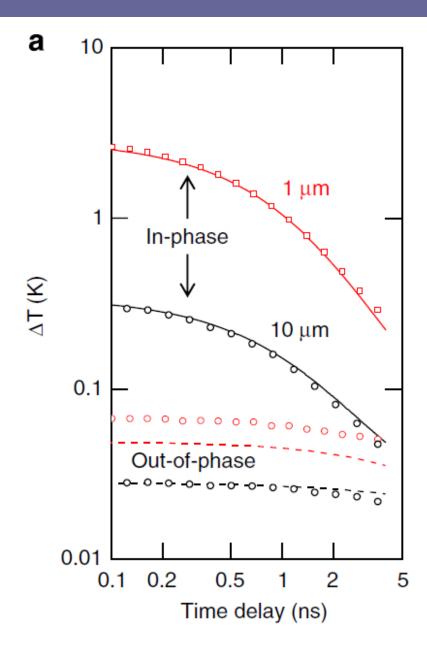
Fourier theory has been observed to fail in TDTR measurements of

semiconductor alloys as a function of fY. K. Koh, D. G. Cahill PRB **76**, 075207 (2008)

silicon below 100 K as a function of w₀ A. Minnich *et al.* PRL **107**, 095901 (2011)

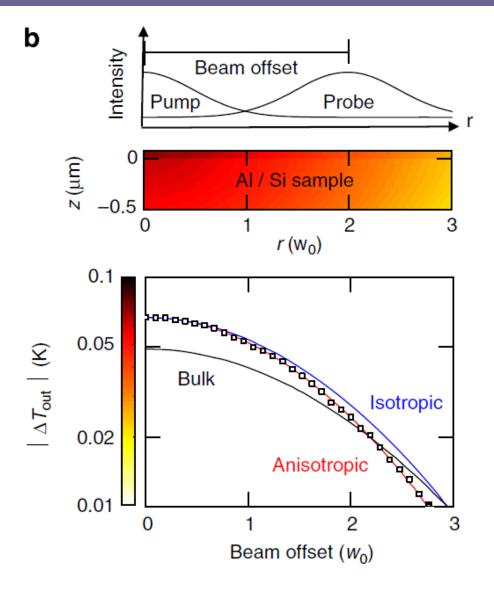
Why does Fourier theory fail with frequency in semiconductor alloys but fail with spot-size in Si at cryogenic temperatures?

I. Anisotropic apparent thermal conductivity of Si



- Conventional TDTR with overlapping pump and probe
- Dependence on spot size is only seen in the out-ofphase signal
- Change in apparent thermal conductivity is from 140 to 105 W m⁻¹ K⁻¹ assuming isotropic transport.

I. Anisotropic apparent thermal conductivity of Si



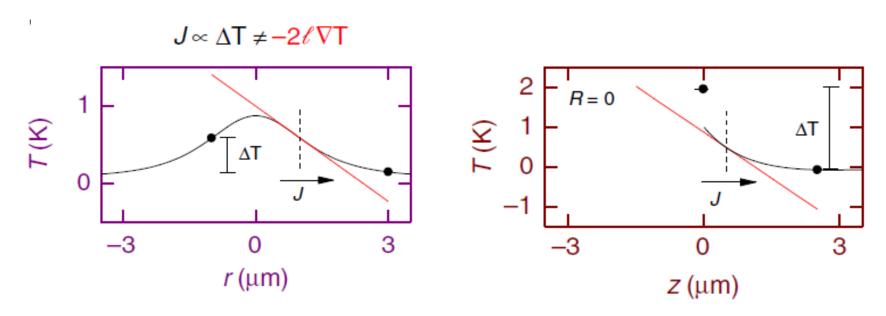
- Beam-offset TDTR cannot be fit with a single value of the apparent thermal conductivity.
- Anisotropic apparent thermal conductivity

$$\Lambda_r = 80 \text{ W m}^{-1} \text{ K}^{-1}$$

$$\Lambda_z = 140 \text{ W m}^{-1} \text{ K}^{-1}$$

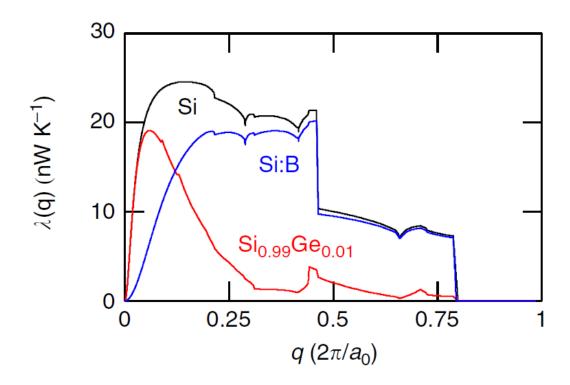
I. Anisotropic apparent thermal conductivity of Si

- Is it physically reasonable that a cubic crystal can have an anisotropic apparent thermal conductivity?
 - No, if all of the heat carriers are diffusive on the length scales of the temperature excursions
 - Yes, if ballistic carriers are significant and there is an interface
- Consider the temperature profiles near the laser spot in the r and z directions



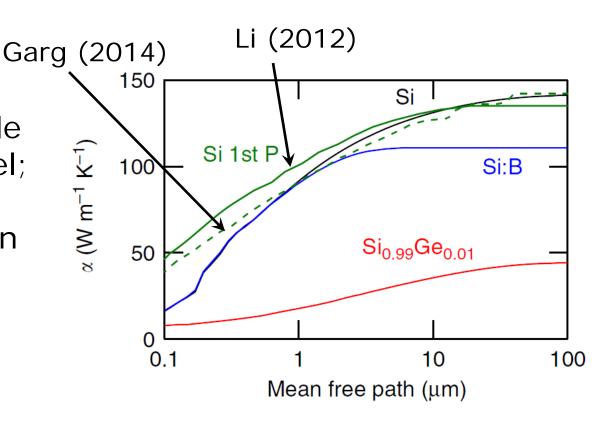
II. Manipulate the spectrum of heat carriers using B and Ge doping of Si.

- B preferentially scatters low frequency phonons (phonon/hole scattering)
- Ge preferentially scatters high frequency phonons (phonon Rayleigh scattering)

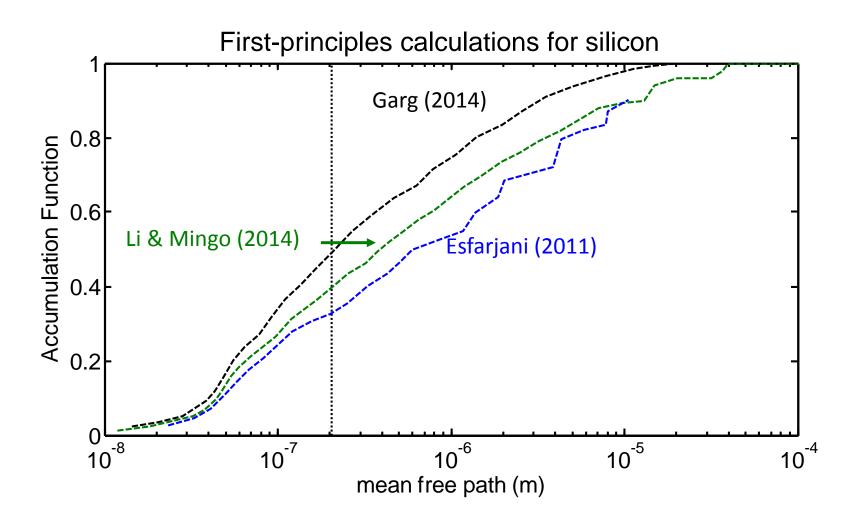


II. Manipulate the spectrum of heat carriers using B and Ge doping of Si.

 We are using a simple relaxation time model; approximates the accumulation function of Si predicted by 1st principle calculations reasonably well

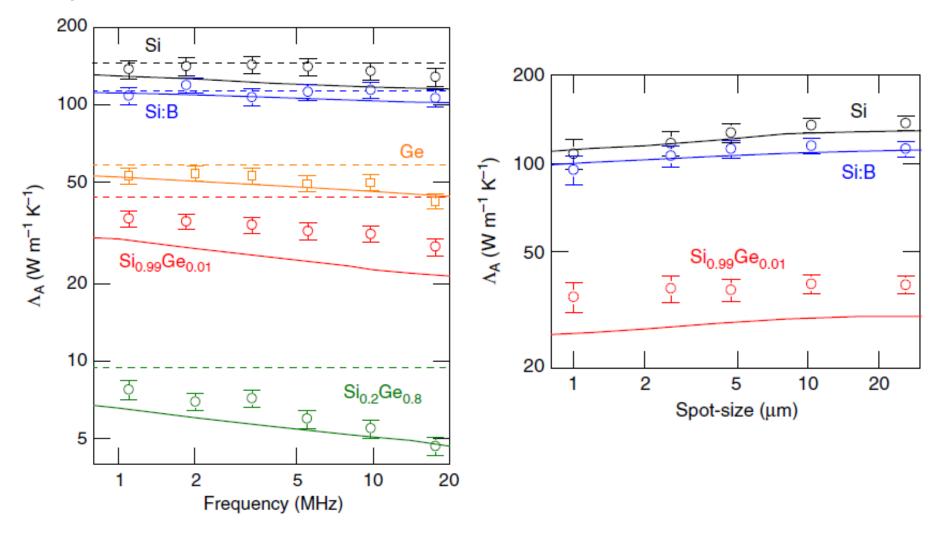


Digression: Differences between the 1st principles calculations are significant



Vary phonons, modulation frequency, spot size

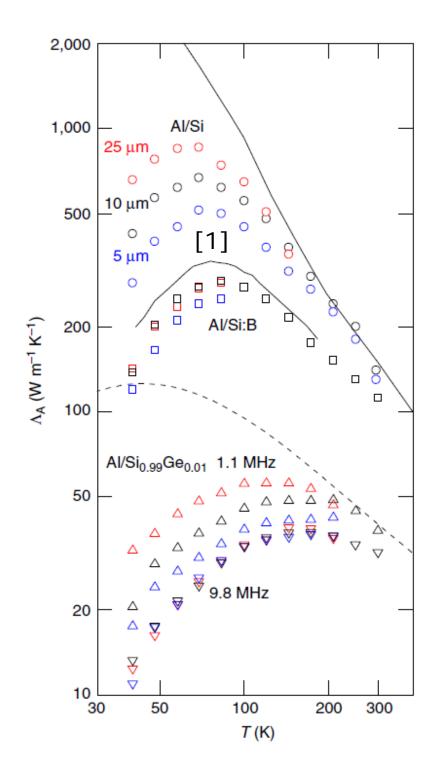
 Low thermal diffusivity of the high frequency phonons is key factor in the failure of Fourier's law in TDTR



...and vary temperature

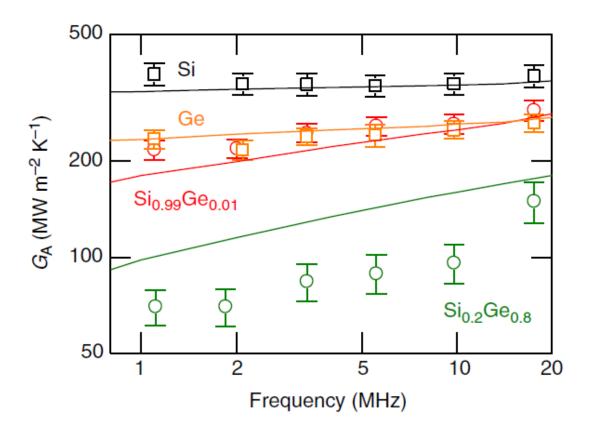
- Differences are more dramatic at low temperatures
 - Fourier law is a good description for Si: B down to 50 K
 - Failure of Fourier's law increases as the distribution of phonon mean-free-paths becomes broader, i.e., from Si: B to Si to SiGe
 - Low thermal diffusivity of high frequency phonons creates greater frequency dependence.

[1] Asheghi (2011)



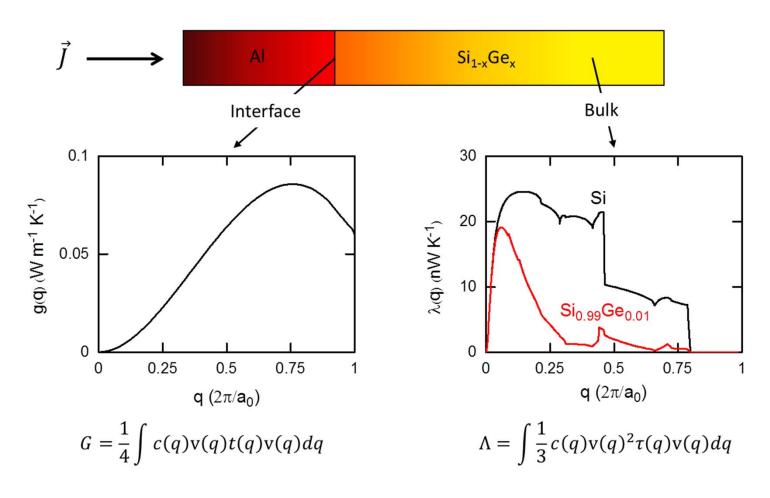
III. Consequences for measurements of interface thermal conductance

- When the thermal diffusivity of the high frequency phonons is small, the apparent interface conductance is reduced and also depends on frequency.
- Radiative boundary condition is not a good description.



III. Consequences for measurements of interface thermal conductance

Different phonons carry heat across the interface than carry heat in the solid



A spatial mismatch exists in the spectral distribution of the heat-current.

III. Consequences for measurements of interface thermal conductance

- For materials with low thermal diffusivity high frequency phonons, the non-equilibrium region created by this mismatch appears in the TDTR measurement as
 - a small interface conductance a low modulation frequency.
 - a reduced thermal conductivity at high modulation frequencies.
- The frequency dependence of the thermal conductivity depends on the transport properties of the interface.

Take-home messages:

- TDTR is surprisingly robust. Even when mean-free-paths are comparable to thermal diffusion lengths, deviations from solutions based on Fourier's law are typically minor.
 - More significant failures in the radial, as opposed to the through thickness direction.
 - More significant failures when the thermal diffusivity of the high frequency phonons is small
 - More significant failures when the thermal conductivity accumulation function is broad.
- Phonon mean-free-path spectroscopy by varying thermal penetration depth?
 - Essentially correct when the thermal diffusivity of the high frequency phonons is small and the accumulation function is broad.

Take-home messages:

- Can we reliably map the apparent thermal conductivity to thermal conductivity accumulation function?
 - Probably "yes" when the accumulation function is relatively broad. But the interface matters.
 - Probably insufficient sensitivity if the accumulation function is narrow; see, e.g., the null result for Si:B at low temperatures